

ABSTRACT OF THE DISCLOSURE

When an exposure shot region cannot converge to a predetermined focus precision while a substrate is scanned, the exposure shot is determined as an error. A wafer stage controller (101) for controlling a shot beam from a pulse laser source (116) stops emission of the pulse laser source (116) if a non-exposure focus error is determined, and executes forced exposure to completely expose the remaining portion of the exposure shot region if an exposure abort focus error is determined.